

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Howard Ge et al.

Serial No.: 10/680,960

Filed: 10/07/2003

For: PHOTORESIST COASTING PROCESS FOR
MICROLITHOGRAPHY

Examiner:

Group Art Unit: 1756

March 10, 2005

Irvine, California 92614

INFORMATION DISCLOSURE STATEMENT

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Dear Sir:

In an attempt to fully comply with the duty of disclosure set forth in 37 C.F.R. § 1.56 and in conformance with 37 C.F.R. §§ 1.97 and 1.98, applicant wishes to bring to the attention of the U.S. Patent Office the following references, which was found during the prosecution of a co-pending PCT International Patent Application:

U.S. Patent No. 5,032,217
U.S. Patent No. 2,046,596
U.S. Patent No. 5,455,062
U.S. Patent No. 5,498,449
U.S. Patent No. 6,403,500
U.S. Patent Application Publication No. 2002/0092917
European Patent Application No. EP 0 654 306
Patent Abstracts of Japan Publication No. 11-010041

KUTCHOUKOV V G ET AL.: "New photoresist coating method for 3-D structured wafers" SENSORS AND ACTUATORS A, ELSEVIER
SEQUOIA S.A., LAUSANNE, CHI, vol. 85, no. 1-3, 25 August 2000
pages 377-383.

Copies of the foreign references, Kutchoukov et al. article and form PTO-A820 are attached.

The undersigned attorney hereby certifies that each item contained in the Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart international application not more than three months prior to filing this statement.

If the Examiner believes that a telephone conference would help further the prosecution of this case, he is respectfully requested to contact the undersigned attorney at the listed telephone number.

I hereby certify that this correspondence is being deposited with the U.S. Postal Service as first class mail in an envelope addressed to: Mail Stop, Commissioner for Patent, PO Box 1450, Alexandria, VA 22313-1450 on March 10, 2005 by: Melissa Gamarra


Signature

Date of Signature: March 10, 2005

Very truly yours,

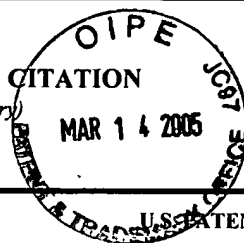
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INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)



Docket Number (Optional)

34261-8500

Application Number

10/680,960

Applicant(s)

Howard Ge et al.

Filing Date

10/07/2003

Group Art Unit

1756

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
		5,032,217	7/16/1991	Tanaka			
		2,046,596	7/7/1936	Zwiebel			
		5,455,062	10/3/1995	Muhlfriedal et al.			
		5,498,449	3/12/1996	Bae			
		6,403,500	6/11/2002	Yu et al.			

U.S. PATENT APPLICATION PUBLICATIONS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
		2002/0092917	7/18/2002	Ko et al.			

FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
		11-010041	19-01-1999	Patent Abstracts of Japan			✓	
		0 654 306	27-05-1994	Europe			✓	

OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

		KUTCHOUKOV V G ET AL.: "New photoresist coating method for 3-D structured wafers" SENSORS AND ACTUATORS A, ELSEVIER SEQUOIA S.A., LAUSANNE, CHI, vol. 85, no. 1-3, 25 August 2000 pages 377-383.

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.